

U.S. Appln. No. 09/300,845 of SATO

In response to the Office Action dated January 17, 2001, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Please delete the specification in its entirety and replace it with the attached Substitute Specification. Both a marked-up version, showing the changes made to the specification, and a clean copy are attached herewith.

IN THE CLAIMS:

Please cancel claims 1-8 without prejudice to or disclaimer of the recited subject matter. Please add new claims 9-15 as follows.

*al* --9. (New) A projection exposure apparatus, comprising:  
an illumination optical system for illuminating a reticle with light from a light source;  
*b* a projection optical system for projecting a pattern of the reticle, as illuminated, onto a substrate;